

L Number	Hits	Search Text	DB	Time stamp
2	10	KUBACKI-RONALD-M-.in. KUBACKI-RONALD-MICHAEL-.in. KUBACKI-R-M-.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 14:08
3	2	("6416938").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 14:08
5	261838	photosensitive photo-sensitive photo adj sensitive	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 14:15
6	3362	silicon adj hydride	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:07
7	40167	monosilane sih4 "sih.sub.4" disilane si2h6 "si.sub.2 h.sub.6" dichlorosilane sih2 cl2 "sih.sub.2 cl.sub.2"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 14:16
8	791792	ethylene c2h4 "c.sub.2 h.sub.4" methane ch4 "ch.sub.4" ethane c2h6 "c.sub.2 h.sub.6" toluene c6h5ch3 "c.sub.6 h.sub.5 ch.sub.3"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 14:17
9	6601	si-h si-si	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:53
10	204466	fragment	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 14:17
11	44644	(oragnic polymer\$3) near2 matrix	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 14:18
12	250570	(silicon si) near4 (oxide dioxide oxidate oxidation oxidiated oxidating)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 14:21
13	3908	430/9,322,324.ccls. 427/487,488,489.ccls. 428/420.ccls. 216/62.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 14:22
4	67	selective with wetting with material	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 14:27
14	3	selective near2 wetting near2 material	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 14:28
15	5963	wetting near2 material	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 14:28
17	19	((selective with wetting with material) (wetting near2 material)) same (photosensitive photo-sensitive photo adj sensitive)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 14:28
16	14	((selective with wetting with material) (wetting near2 material)) with (photosensitive photo-sensitive photo adj sensitive)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 14:54

18	5	((selective with wetting with material) (wetting near2 material)) same (photosensitive photo-sensitive photo adj sensitive) not ((selective with wetting with material) (wetting near2 material)) with (photosensitive photo-sensitive photo adj sensitive))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 14:54
19	26108	plasma-deposit\$5 plasma near2 deposit\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:00
20	68	(photosensitive photo-sensitive photo adj sensitive) with (plasma-deposit\$5 plasma near2 deposit\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:01
21	118	(photosensitive photo-sensitive photo adj sensitive) same ((silicon adj hydride) (monosilane sih4 "sih.sub.4" disilane si2h6 "si.sub.2 h.sub.6" dichlorosilane sih2 cl2 "sih.sub.2 cl.sub.2")) same (ethylene c2h4 "c.sub.2 h.sub.4" methane ch4 "ch.sub.4" ethane c2h6 "c.sub.2 h.sub.6" toluene c6h5ch3 "c.sub.6 h.sub.5 ch.sub.3")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:11
23	6	(430/9,322,324.ccls. 427/487,488,489.ccls. 428/420.ccls. 216/62.ccls.) and ((selective with wetting with material) ((photosensitive photo-sensitive photo adj sensitive) with (plasma-deposit\$5 plasma near2 deposit\$5)) ((photosensitive photo-sensitive photo adj sensitive) same ((silicon adj hydride) (monosilane sih4 "sih.sub.4" disilane si2h6 "si.sub.2 h.sub.6" dichlorosilane sih2 cl2 "sih.sub.2 cl.sub.2")) same (ethylene c2h4 "c.sub.2 h.sub.4" methane ch4 "ch.sub.4" ethane c2h6 "c.sub.2 h.sub.6" toluene c6h5ch3 "c.sub.6 h.sub.5 ch.sub.3")))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:10
25	1	((photosensitive photo-sensitive photo adj sensitive) same ((silicon adj hydride) (monosilane sih4 "sih.sub.4" disilane si2h6 "si.sub.2 h.sub.6" dichlorosilane sih2 cl2 "sih.sub.2 cl.sub.2")) same (ethylene c2h4 "c.sub.2 h.sub.4" methane ch4 "ch.sub.4" ethane c2h6 "c.sub.2 h.sub.6" toluene c6h5ch3 "c.sub.6 h.sub.5 ch.sub.3")) same ((silicon si) near4 (oxide dioxide oxidate oxidation oxidated oxidating))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:11
24	40	((photosensitive photo-sensitive photo adj sensitive) same ((silicon adj hydride) (monosilane sih4 "sih.sub.4" disilane si2h6 "si.sub.2 h.sub.6" dichlorosilane sih2 cl2 "sih.sub.2 cl.sub.2")) same (ethylene c2h4 "c.sub.2 h.sub.4" methane ch4 "ch.sub.4" ethane c2h6 "c.sub.2 h.sub.6" toluene c6h5ch3 "c.sub.6 h.sub.5 ch.sub.3")) and ((silicon si) near4 (oxide dioxide oxidate oxidation oxidated oxidating))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:13
26	2718816	organo-silicon organosilicon silicon si organic	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:14
27	30	((photosensitive photo-sensitive photo adj sensitive) with (plasma-deposit\$5 plasma near2 deposit\$5)) with (organo-silicon organosilicon silicon si organic)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:16

28	100617	sensitive near (photo radiation energy light)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:20
29	82	((photosensitive photo-sensitive photo adj sensitive) (sensitive near (photo radiation energy light))) with (plasma-deposit\$5 plasma near2 deposit\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:21
30	13027	si-contain\$3 silicon-contain\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:22
31	35	((((photosensitive photo-sensitive photo adj sensitive) (sensitive near (photo radiation energy light))) with (plasma-deposit\$5 plasma near2 deposit\$5)) with ((organo-silicon organosilicon silicon si organic) (si-contain\$3 silicon-contain\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:22
33	30	((((photosensitive photo-sensitive photo adj sensitive) (sensitive near (photo radiation energy light))) with (plasma-deposit\$5 plasma near2 deposit\$5)) with ((organo-silicon organosilicon silicon si organic) (si-contain\$3 silicon-contain\$3))) and ((monosilane sih4 "sih.sub.4" disilane si2h6 "si.sub.2 h.sub.6" dichlorosilane sih2 cl2 "sih.sub.2 cl.sub.2") (ethylene c2h4 "c.sub.2 h.sub.4" methane ch4 "ch.sub.4" ethane c2h6 "c.sub.2 h.sub.6" toluene c6h5ch3 "c.sub.6 h.sub.5 ch.sub.3") (si-h si-si) fragment ((oragnic polymer\$3) near2 matrix) ((silicon si) near4 (oxide dioxide oxidate oxidation oxidiated oxidating))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:30
35	10	((((photosensitive photo-sensitive photo adj sensitive) (sensitive near (photo radiation energy light))) with (plasma-deposit\$5 plasma near2 deposit\$5)) with ((organo-silicon organosilicon silicon si organic) (si-contain\$3 silicon-contain\$3))) and (((silicon adj hydride) (monosilane sih4 "sih.sub.4" disilane si2h6 "si.sub.2 h.sub.6" dichlorosilane sih2 cl2 "sih.sub.2 cl.sub.2")) with (ethylene c2h4 "c.sub.2 h.sub.4" methane ch4 "ch.sub.4" ethane c2h6 "c.sub.2 h.sub.6" toluene c6h5ch3 "c.sub.6 h.sub.5 ch.sub.3")))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:31
36	5	(si-h si-si) and (((photosensitive photo-sensitive photo adj sensitive) (sensitive near (photo radiation energy light))) with (plasma-deposit\$5 plasma near2 deposit\$5)) with ((organo-silicon organosilicon silicon si organic) (si-contain\$3 silicon-contain\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:37
37	5	(si-h si-si) with fragment	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:38
38	6	(si-h si-si) with ((oragnic polymer\$3) near2 matrix)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:49
39	13	(si-h si-si) same ((oragnic polymer\$3) near2 matrix)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:50

40	7	((si-h si-si) same ((oragnic polymer\$3) near2 matrix)) not ((si-h si-si) with ((oragnic polymer\$3) near2 matrix))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:49
41	2178	(si-h si-si) same (organic polymer\$3 matrix)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:54
42	4	((photosensitive photo-sensitive photo adj sensitive) (sensitive near (photo radiation energy light))) with (plasma-deposit\$5 plasma near2 deposit\$5)) and ((si-h si-si) same (organic polymer\$3 matrix))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:54
43	11265	sih sisi	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:53
44	2201	(sih sisi) same (organic polymer\$3 matrix)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:54
45	3	((photosensitive photo-sensitive photo adj sensitive) (sensitive near (photo radiation energy light))) with (plasma-deposit\$5 plasma near2 deposit\$5)) and ((sih sisi) same (organic polymer\$3 matrix))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:54